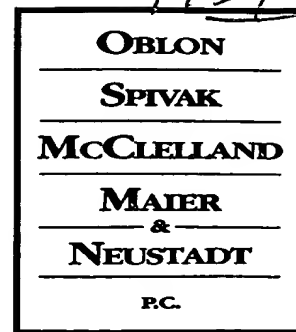




Docket No.: 0160-0193-0 PCT

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231



ATTORNEYS AT LAW

RE: Application Serial No.: 09/463,961
Applicants: Hiroshi IKEDA, et al.
Filing Date: May 25, 2000
For: PROCESS AND APPARATUS FOR TREATING
SEMICONDUCTOR PRODUCTION EXHAUST
GASES
Group Art Unit: 1754
Examiner: Johnson, Edward M.

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SIR:


Attached hereto for filing are the following papers:

**Response to Restriction Requirement
Request for Extension of Time - One Month
International Preliminary Examination Report**

Our check in the amount of \$110.00 is attached covering any required fees. In the event any variance exists between the amount enclosed and the Patent Office charges for filing the above-noted documents, including any fees required under 37 C.F.R. 1.136 for any necessary Extension of Time to make the filing of the attached documents timely, please charge or credit the difference to our Deposit Account No. 15-0030. Further, if these papers are not considered timely filed, then a petition is hereby made under 37 C.F.R. 1.136 for the necessary extension of time. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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